

## Important new developments

Atlas 46 - negative photoresists up to 100 µm stable resist structures

AR-N 4600

EOS 72 - positive e-beam resist, CAR high resolution, highest sensitive

SX AR-P 7200

Phoenix 81 - thermostructurable positive resist for NanoFrazor application

AR-P 8100

Medusa 82 - negative e-beamres. adjusted HSQ, more prozess stability or. sensitive, high resolution

SX AR-N 8200, 8250

Protective coating, 40% KOH-, 50% HF-resist.

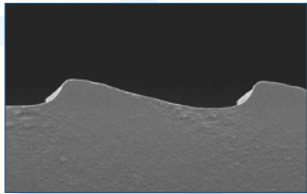
SX AR-PC 5000/41

Temperature-stable negative photoresist up to 300 °C, suitable für 2-layer systems

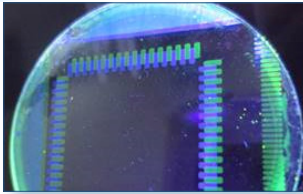
SX AR-N 4340/7

Fluorescent photo- and e-beam resists

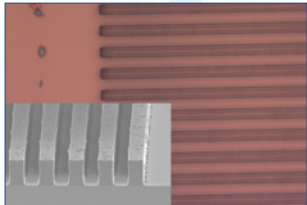
SX AR-P/N 8500



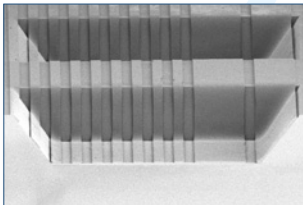
Sinusoidal profiles with AR-N 7720.30



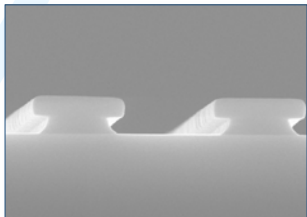
3 different fluorescent atlas structures



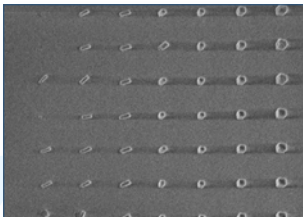
Atlas 46 R 5 µm line & space, structures are easy removable



AR-N 2220 resist structures in 200 µm deep etched trenches



Thermostable 2-Layer lift-off systems with AR-BR 5460 and SX AR-N 4340/7



60-150 nm squares (100 nm height) on glass with AR-N 7700.08 and AR-PC 5091.02

ALLRESIST GmbH -  
Company for chemical products for microstructures

Foundation: Oktober 16 1992, HRB 7805 AG Frankfurt (Oder)

Managing directors: Brigitte and Matthias Schirmer

Integrated management system: Quality management DIN EN ISO 9001:2015, Eco-Management DIN EN ISO 14001:2015

Memberships in science- and trade associations: Silicon Saxony, iq Brandenburg, Verein Sichere Identität, IVAM

Prizes & Awards:

Ludwig-Erhard-Preis

Qualitätspreis Berlin-Brandenburg

Innovation Prize Brandenburg

Deutschlands Kundenchampions

Deutschlands Mitarbeiterchampions

Exzellente Wissensorganisation

Technologietransferpreis Brandenburg

Zukunftspreis Ostbrandenburg

Entrepreneur of the Federal State of Brandenburg



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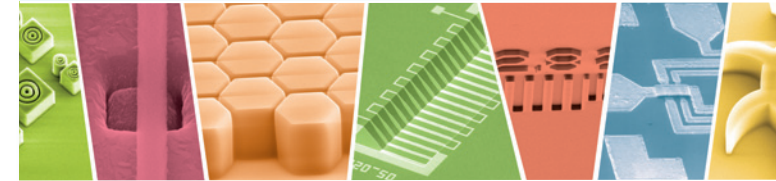


**ALLRESIST**



*Innovation  
Creativity  
Customer-specific solution*

Resists and Process chemicals  
for optical and electron beam lithography



over **25** years **Allresist**

*Innovation, creativity, customer-specific solutions*



Deutschlands  
Kundenchampions  
2010



Deutschlands  
Mitarbeiterchampions  
2012



Umweltpartnerschaft  
Brandenburg



EXZELLENT  
WISSENSORGANISATION



BRANDENBURG  
INNOVATIONSPREIS



## Product profile ALLRESIST

Development, production and distribution of photo- & e-beam resists as well as process chemicals for the manufacturing of electronic components (chips)

- Wide range of products - resists for (almost) all standard technologies
- Process-specific resists according to customer's requests für industrial - unique selling proposition
- Development of innovative products for new application and technologies
- Particular focus on industrial research, project development in cooperation with research
- Individual, competent product- and technology consulting
- Short delivery times (products in stock are delivered promptly)
- Customer-oriented package sizes of 250 ml, test samples of 100 ml



Evaluation of customer requirements and new products. Strategic discussion in the steering committee

## Customer-specific resists

ALLRESIST will take your special demands into consideration already during conception and development of new resists.

For industry customers, Allresist develops tailor-made resists or modifies standard resists according to the respective technology requirements.



Introduction of customer-specific resists

You will find detailed product information together with a collection of Resist Wiki, AR NEWS, FAQ and EU safety data sheets at [www.allresist.com](http://www.allresist.com).

In addition to our resists, we offer thinner, developer, stopper, remover and adhesion promoter as optimally resist-adapted process chemicals.

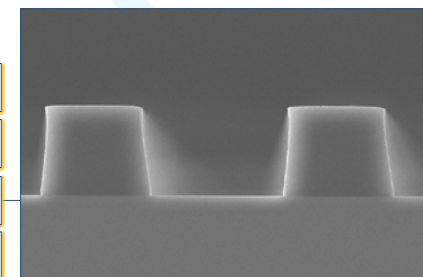
Allresist continuously develops new products. Please contact us!

As of 01/21

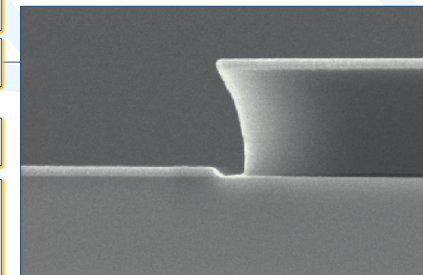
## Product summary

Positive photoresists, i, g-line	Spray coating for various applications	[0.5 - 10]	AR-P 1210, 1220, 1230
	Mask production, fine gradations, high resolution	1.0 ; 0.6 ; 0.1	AR-P 3110, 3120, 3170
	Thick resist of high dimens. accuracy up to 40/100/20 µm	10 ; 5 ; 10	AR-P 3210, 3250, 3220
	Wide process range, high resolution	2.0 ; 1.4	AR-P 3510 (T), 3540 (T)
	High contrast, highest resolution, sub-µm	1.4	AR-P 3740
	Undercut structures (one layer lift-off)	5.0 ; 1.0	AR-P 5320, 5350
Special systems	Protective coating, 40 % KOH-etch-stable	2.2 ; 2.8	AR-PC 504, 5040
	Conductive protective coatings for e-beam	0,04	Electra 92 AR-PC 5090, 5091
	Bottom resist for 2-layer lift-off system (pos/neg.)	1.0 ; 0.5	AR-BR 5460, 5480
Neg. photoresists	Spray coating for various applications	[0.5 - 10]	AR-P 2210, 2220, 2230
	Highest sensitivity, high resolution, i-line, g-line	1.4	AR-N 4340
	Thick films up to 100 / 50 / 20 µm i-line, e-beam easy removal, Profiles with high edge steepness for excellent resolution	50 ; 25 ; 10 (1000 rpm)	CAR 44 AR-N 4400-50, -25 AR-N 4400-10, -05
Positive e-beam resists	Copolymer PMMA/MA 33%, highest resolution	0.09 .... 1.75	AR-P 617
	PMMA 50K, 200K, 600K, 950K, highest resolution chlorobenzene (1), anisole (2), ethyl lactate (9)	0.01 .... 1.87	AR-P 641-671, 632-672 AR-P 639-679
	Styrene acrylate, highest resolution, high sensitivity, very plasma etching-resistant	0.08 ... 0.80	CSAR 62 AR-P 6200
	Thick PMMA films up to 100 µm, deep UV	350 rpm: 45-95	AR-P 6510
Neg e-beam resist	Mix&match, etching-resistant, high resolution	0.4 ; 0.1	AR-N 7500
	Mix&match, etching-resistant, highest resolution	0.4 ; 0.2 ; 0.1	AR-N 7520 (new)
	CAR, high resolution, steep gradation, digit. image	0.4 ; 0.1	AR-N 7700
	CAR, high resolution, low contrast	1.4 ; 0.25	AR-N 7720

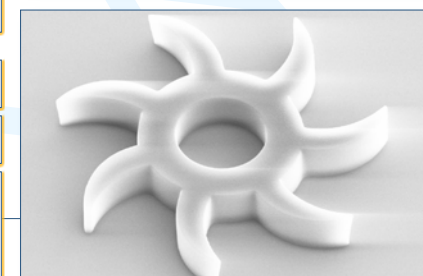
D<sub>0</sub> [µm] 4000 rpm



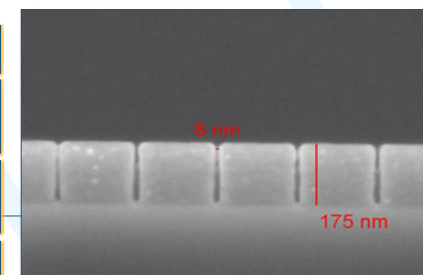
20 µm high lines with AR-P 3220



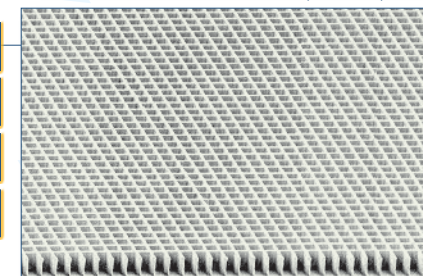
Lift-off-structures with AR-P 5350



Turbine wheel 500 µm with AR-N 4400-50 (CAR 44)



10 nm trenches with AR-P 6200.09 (CSAR 62)



70 nm structures with AR-N 7500.18